

A Compact Model of Ballistic CNFET for Circuit Simulation

B. C. Paul^{††}, S. Fujita[†], M. Okajima[†], and T. Lee[†]

[‡]Center for Integrated Systems, Stanford University
Stanford, CA

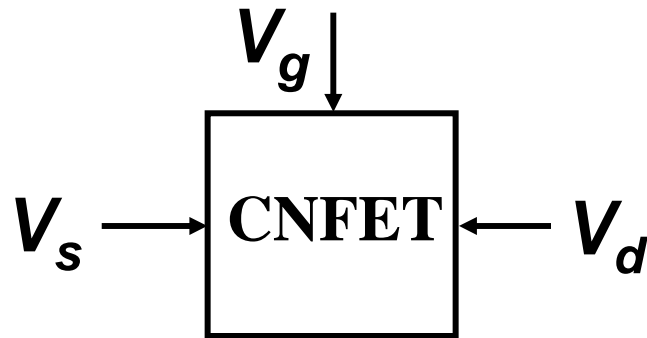
[†]Toshiba America Research
2590 Orchard Parkway, San Jose, CA



TOSHIBA

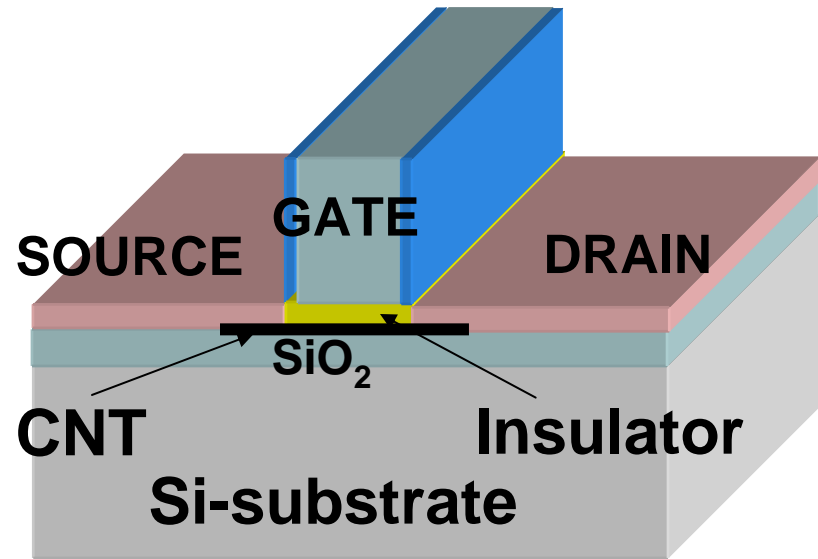
Objective

To achieve **ANALYTICAL** expression for device electrostatics



$$I_D = f_1(V_g, V_d, V_s)$$

$$C = f_2(V_g, V_d, V_s)$$



TOSHIBA

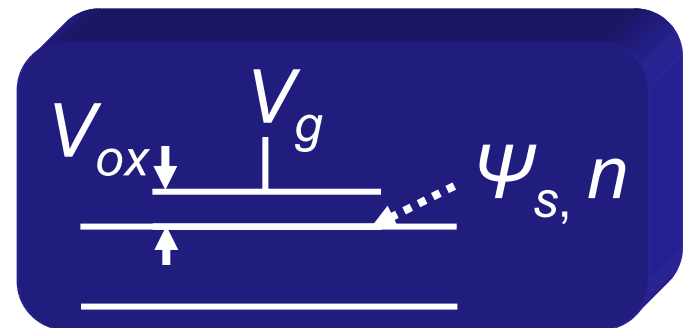
Challenges

- To obtain **CLOSED** form integral

$$n_p = N_0 \sum_{v_i=v_s, v_d} \left[\int_0^\infty \frac{dz}{1 + e^{\left(\sqrt{z^2 + \varepsilon_{c,p}^2} - (\varphi_s - v_i)\right)}} \right]$$

- Solving **SELF- CONSISTENT** equations

$$\psi_s = V_{gs} - V_{INS} = V_{gs} - \frac{Q_{CNT}}{C_{INS}}$$



TOSHIBA

Approximate Solution

$$Q_{CNT} = e^{(\alpha_0 + \alpha_1 \psi_s)} \quad \text{for } V_{gs} < V_T$$

$$Q_{CNT} = \lambda_0 + \lambda_1(\psi_s - \psi_T) + \lambda_2(\psi_s - \psi_T)^2$$

for $V_{gs} > V_T$

Effect of V_{ds} is insignificant for $V_{ds} > 3k_B T/q$

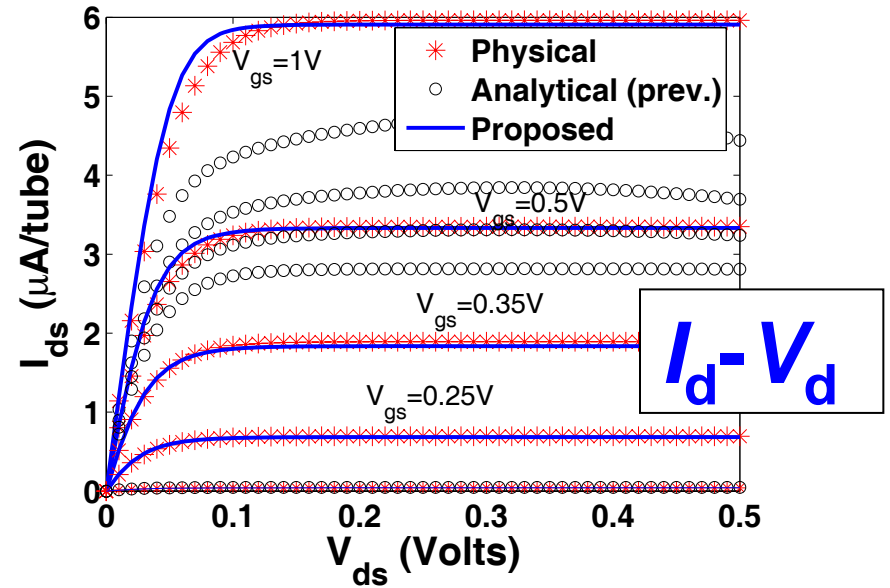
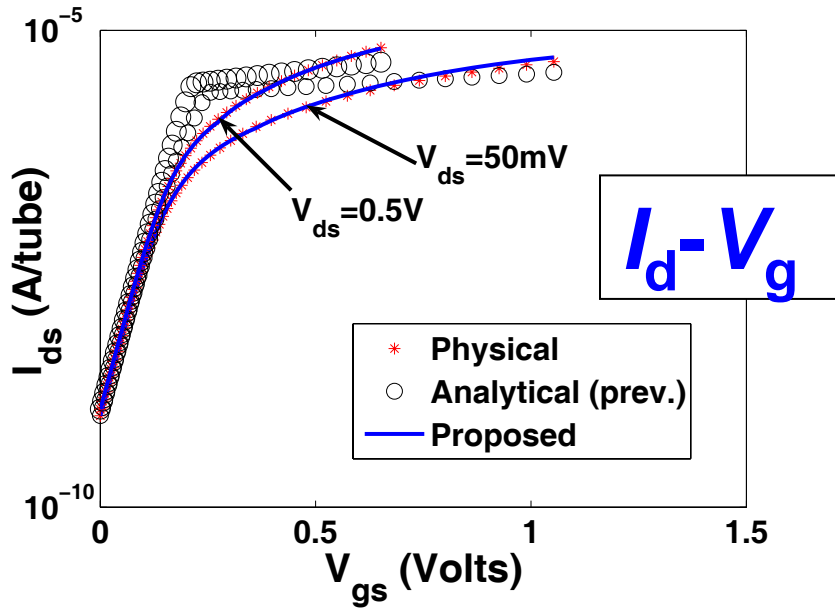


TOSHIBA

Simulation Results

Diameter = 2nm

$C_{ox} = 48.3\text{pF/m}$, $V_T = 0.3\text{V}$



TOSHIBA